

PLC50

Cost-effective, ice- and condensation-free manual wafer probing down to 4 K

Microscope

- Zoom microscope with camera and illumination
- Video monitor

Cryogenic system

- Temperature range: 4 to 400 K
- Continuous flow cryostat with supply tank transfer line and exhaust pumps
- Temperature controller

Vacuum chamber

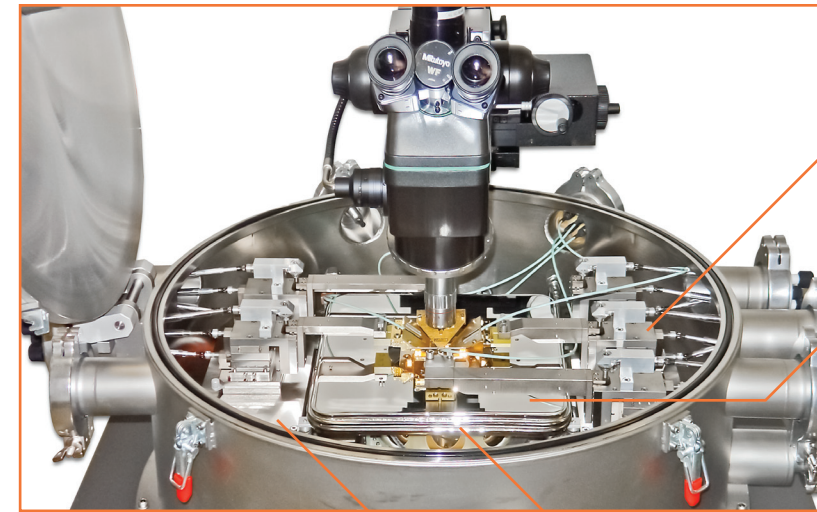
- Wide pressure range from atmospheric to high vacuum (10^{-5} mbar)
- Hinged chamber lid for easy access
- Space for cabling and additional electronics inside
- DC and RF electrical feed through flanges

Vacuum control

- High-vacuum pump unit
- Turbo molecular pump directly connected to the chamber

Vibration isolated mainframe

- Pneumatic vibration damping
- Rigid framework and base plate



Positioners

- Inside vacuum chamber for excellent mechanical stability
- Linear backlash-free movement
- Reliable and repeatable contact

Chuck stage

- High-precision, linear two-axis stage for high throughput
- XY travel up to 80 mm
- Easy to control from outside the chamber
- Wafer/sample size up to 100 mm
- Optional triax add-on for accurate measurements over chuck

Measurement setup

- DC and RF configuration
- SIGMA™ integration for excellent measurement accuracy
- Example setup with four RF Probes

Cryogenic shield

- Surrounds heat exchanger to limit outside radiation
- Independent temperature control to eliminate gas and particle condensation

Probe platen

- Contact-separation z-movement for step and repeat capability
- Space for up to six positioners

